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Improved Schottky behavior of GaN nanorods using hydrogen plasma treatment

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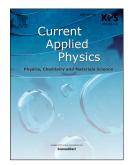
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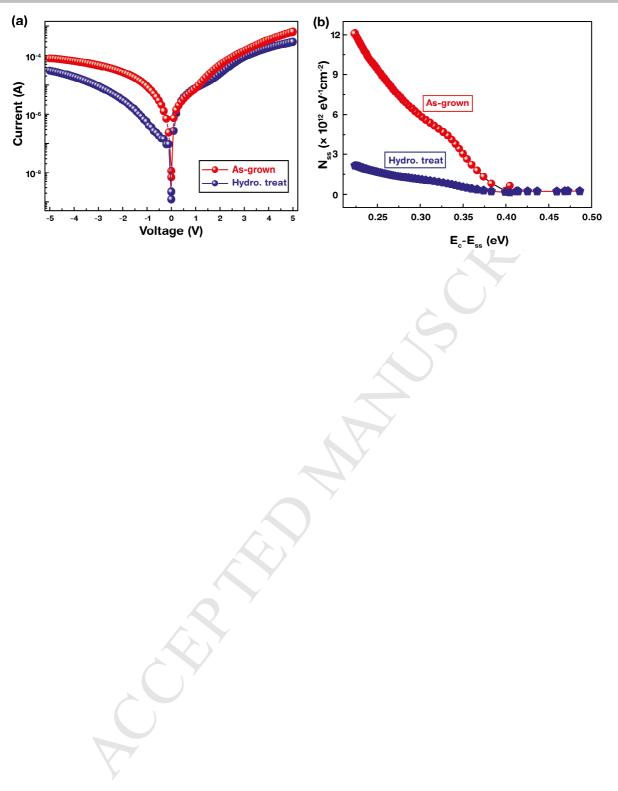
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